

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re patent application of

Tae-Hee CHOE, et al.

Serial No.

*[Division of Serial No. 09/989,112, filed November 21, 2001]*

Filed: November 17, 2003

For: SOI SUBSTRATE HAVING AN ETCH STOP LAYER, AND FABRICATION METHOD  
THEREOF, SOI INTEGRATED CIRCUIT FABRICATED THEREON, AND  
METHOD OF FABRICATING SOI INTEGRATED CIRCUIT USING THE SAME

**PRELIMINARY AMENDMENT**

Commissioner for Patents

Alexandria, VA 22313-1450

Sir:

Prior to calculation of the statutory filing fee, kindly amend the application identified above as follows:

**IN THE CLAIMS**

Cancel Claims 26-41 without prejudice or disclaimer.

Amendments to the claims are reflected in the listing of claims which begins on page 2 of this Amendment.